

EV317136178

Inventor: Demetrius Sarigiannis, Garo J. Derderian and Cem Basceri
Title: Methods of Forming Layers Over Substrates; and Methods
of Forming Trenched Isolation Regions
Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT

PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, the Examiner's attention is directed to the references listed on the attached Form PTO-1449 and copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Date: 6/26/2003

Attorney: 

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Form PTO-1449

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FOREIGN PATENT DOCUMENTS

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|--|----|-----------------|----------|---------|-------|----------|-------------|----|
| | | | | | | | Yes | No |
| | AF | WO 02/27063 A2 | 04/04/02 | WIPO | | | | |
| | AG | | | | | | | |

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

| | | | | | | | | |
|--|----|--|---|--|--|--|--|--|
| | AH | | *Atomic Layer Deposition of SiO ₂ Using Catalyzed And Uncatalyzed Self-Limiting Surface Reactions*, J.W. Klaus et al; Surface Review | | | | | |
| | | | and Letters, Vol. 6, Nos. 3 & 4 (1999) pp. 435-448 | | | | | |
| | AI | | Self-limiting chemical vapor deposition of an ultra-thin silicon oxide film using tri-(tert-butoxy)silanol*, K.A., Miller et al; | | | | | |
| | | | Thin Solid Films 397 (2001): pp. 78-82) | | | | | |
| | AJ | | *Reactive Deposition of Metal Thin Films within Porous Supports from Supercritical Fluids*, Neil E. Fernandes et al.; Chem Mater. 2001; | | | | | |
| | | | 13, pp. 2023-2031 | | | | | |
| | AK | | *Supercritical CO ₂ Processing for Submicron Imagine of Fluoropolymers*, Narayan Sundararajan et al; Chem. Mater. 2000; 12; | | | | | |
| | | | pg. 41-48 | | | | | |
| | AL | | *Supercritical carbon dioxide assisted aerosolization for thin film deposition, fine powder generation, and drug delivery*, | | | | | |
| | | | C.Y. Xu et al.; P.T. Anastas; T.C. Williamson, Green Chemistry, 5. pp. 313-335; Oxford University Press, Oxford 1998 | | | | | |
| | AM | | *Supercritical Fluid Transport-Chemical Deposition of Films*, Brian N. Hansen et al.; Chem Mater. 1992; 4: pp. 749-752 | | | | | |
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EXAMINER

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